

Sheet 1 of 1

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO.	SERIAL NO.			
				AMAT 5264/5830				
				APPLICANT	Cheng Guo et al.			
				FILING DATE	GROUP			
				October 27, 2000	1752			
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA							
	AB							
	AC							
	AD							
	AE							
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	AG							
	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY		CLASS	SUBCLASS	TRANSLATION YES      NO
	AL							
	AM							
	AN							
	AO							
	AP							
OTHER INFORMATION (including Author, Title, Date, Pertinent Pages, Etc.)								
<i>SLM</i>	AR	Article entitled "New approach to projection-electron lithography with demonstrated 0.1 um linewidth" by S.D. Berger et al., Applied Physics Letters, 57 (2), July 1990, pages 153-155.						
<i>SLM</i>	AS	Article entitled "Projection electron-beam lithography: A new approach", by S.D. Berger et al., J. Vac. Sci. Technol. B 9 (6), Nov/Dec 1991, pages 2996-2999.						
	AT							
EXAMINER <i>Mohamedulla</i>				DATE CONSIDERED <i>2/23/02</i>				
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								